

EAST Search History

EAST Search History (Prior Art)

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L2	28	semiconductor AND Substrate WITH Mgo WITH silicon wafer	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/27 05:29
L3	0	semiconductor AND common\$4 WITH substrate WITH Mgo WITH silicon wafer	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/27 05:29
L4	76	semiconductor AND Substrate SAME Mgo SAME silicon wafer	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/27 05:30
L5	29	4 and oxide.ab.	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/27 05:31
L6	34	4 and silicon oxide	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/27 05:35
L7	567	semiconductor WITH device AND Substrate SAME (Mgo OR Rh OR Ir OR Pt OR "SRTIO.sub.3" OR "IRO.sub.2" OR "LaNiO.sub.3") SAME (silicon wafer OR Si wafer)	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/27 05:40
L8	9	7 and silicon oxide.ab.	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/27 05:40
L9	94	7 and TEOS	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/27 05:41
L10	370	semiconductor WITH device AND Substrate SAME (Mgo OR Rh OR Pt OR "SRTIO.sub.3" OR "IRO.sub.2" OR "LaNiO.sub.3") SAME (silicon wafer OR Si wafer)	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/27 05:42
L11	44	10 and TEOS	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/27 05:42
L12	3	semiconductor WITH device AND Substrate SAME (Mgo OR Rh OR Pt OR "SRTIO.sub.3" OR "IRO.sub.2" OR "LaNiO.sub.3") SAME (silicon wafer OR Si wafer) WITH preferabl\$3	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/27 05:43

L13	0	semiconductor WITH device AND Substrate SAME (Mgo OR Rh OR PT OR "SRTIO.sub.3" OR "IRO.sub.2" OR "LaNiO.sub.3") SAME (silicon wafer OR Si wafer) SAME generally	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/27 05:43
L14	17	semiconductor WITH device AND Substrate SAME (Mgo OR Rh OR PT OR "SRTIO.sub.3" OR "IRO.sub.2" OR "LaNiO.sub.3") SAME (silicon wafer OR Si wafer) SAME common\$3	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/27 05:44
L15	9	semiconductor WITH device AND substrate SAME (Mgo OR Rh OR PT OR "SRTIO.sub.3" OR "IRO.sub.2" OR "LaNiO.sub.3") SAME preferabl \$4 AND ("SIO.sub.2" OR silicon oxide OR silicon dioxide) WITH (film OR layer OR coat\$4).ab.	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/27 05:45
L16	173	semiconductor WITH device AND substrate SAME (Mgo OR Rh OR PT OR "SRTIO.sub.3" OR "IRO.sub.2" OR "LaNiO.sub.3") SAME preferabl \$4 AND ("SIO.sub.2" OR silicon oxide OR silicon dioxide) WITH (film OR layer OR coat\$4).bsum.	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/27 05:46
L17	463	semiconductor WITH device AND (substrate OR base) SAME (Mgo OR Rh OR PT OR "SRTIO.sub.3" OR "IRO.sub.2" OR "LaNiO.sub.3") AND ("SIO.sub.2" OR silicon oxide OR silicon dioxide) WITH (film OR layer OR coat\$4).ab.	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/27 05:48
L18	315	semiconductor WITH device AND (substrate OR base) WITH (Mgo OR Rh OR PT OR "SRTIO.sub.3" OR "IRO.sub.2" OR "LaNiO.sub.3") AND ("SIO.sub.2" OR silicon oxide OR silicon dioxide) WITH (film OR layer OR coat\$4).ab.	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/27 05:48
L19	29	semiconductor WITH device AND (substrate OR base) WITH (Mgo OR Rh OR PT OR "SRTIO.sub.3" OR "IRO.sub.2" OR "LaNiO.sub.3") AND ("SIO.sub.2" OR silicon oxide OR silicon dioxide) WITH (film OR layer OR coat\$4).ab. and teos	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/27 05:48

L20	2	semiconductor WITH device AND (substrate OR base) WITH (Mgo OR "SRTIO.sub.3" OR "IRO.sub.2" OR "LaNiO.sub.3") AND ("SiO.sub.2" OR silicon oxide OR silicon dioxide) WITH (film OR layer OR coat\$4).ab. and teos	US-PGPUB; USPAT; USCCR	ADJ	ON	2010/08/27 05:49
L21	208	semiconductor WITH device AND (substrate OR base) WITH (Mgo OR "SRTIO.sub.3" OR "IRO.sub.2" OR "LaNiO.sub.3") AND ("SiO.sub.2" OR silicon oxide OR silicon dioxide) WITH (film OR layer OR coat\$4).ab.	US-PGPUB; USPAT; USCCR	ADJ	ON	2010/08/27 05:50
L22	202	semiconductor WITH device AND (substrate) WITH (Mgo OR "SRTIO.sub.3" OR "IRO.sub.2" OR "LaNiO.sub.3") AND ("SiO.sub.2" OR silicon oxide OR silicon dioxide) WITH (film OR layer OR coat\$4).ab.	US-PGPUB; USPAT; USCCR	ADJ	ON	2010/08/27 05:50
L23	188	semiconductor WITH device AND (substrate OR base) WITH (Mgo OR "SRTIO.sub.3" OR "IRO.sub.2" OR "LaNiO.sub.3") AND ("SiO.sub.2" OR silicon oxide OR silicon dioxide) WITH (film OR layer OR coat\$4).ab. AND CVD	US-PGPUB; USPAT; USCCR	ADJ	ON	2010/08/27 05:56
L24	202	semiconductor WITH device AND (substrate) WITH (Mgo OR "SRTIO.sub.3" OR "IRO.sub.2" OR "LaNiO.sub.3") AND ("SiO.sub.2" OR silicon oxide OR silicon dioxide) WITH (film OR layer OR coat\$4).ab.	US-PGPUB; USPAT; USCCR	ADJ	ON	2010/08/27 05:59
L25	183	semiconductor WITH device.bsm. AND (substrate) WITH (Mgo OR "SRTIO.sub.3" OR "IRO.sub.2" OR "LaNiO.sub.3") AND ("SiO.sub.2" OR silicon oxide OR silicon dioxide) WITH (film OR layer OR coat\$4).ab.	US-PGPUB; USPAT; USCCR	ADJ	ON	2010/08/27 05:59
L26	8	(substrate) WITH (Mgo OR "SRTIO.sub.3" OR "IRO.sub.2" OR "LaNiO.sub.3") AND (vapor deposition OR CVD) SAME ("SiO.sub.2" OR silicon oxide OR silicon dioxide) WITH (film OR layer OR coat\$4).ab.	US-PGPUB; USPAT; USCCR	ADJ	ON	2010/08/27 06:02

L27	9	(substrate) WITH (Mgo OR "SrTiO.sub.3" OR "IRO.sub.2" OR "LaNiO.sub.3") AND (vapor deposition OR CVD) SAME ("SiO.sub.2" OR silicon oxide OR silicon dioxide).ab.	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/27 06:03
S1	1	(10/569470).APP.	US-PGPUB; USPAT; USOCR	OR	OFF	2010/08/26 19:15
S2	1	("20030012875").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2010/08/26 21:19
S3	213	decompos\$6 WITH mixture WITH (gas OR vapor OR vapour) AND oxide WITH (film OR layer OR coat\$4).ab.	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/26 21:37
S4	1	(separat\$4 OR apart OR remote\$4) WITH decompos\$6 WITH mixture WITH (gas OR vapor OR vapour) AND oxide WITH (film OR layer OR coat\$4).ab.	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/26 21:44
S5	37	(separat\$4 OR apart OR remote\$4) WITH decompos\$6 WITH mixture WITH (gas OR vapor OR vapour) AND oxide WITH (film OR layer OR coat\$4).bsum.	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/26 21:45
S6	51	remote\$4 WITH decompos\$6 WITH (gas OR vapor OR vapour) AND oxide WITH (film OR layer OR coat\$4).bsum.	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/26 21:46
S7	82	("4872947" "4951601" "5403434" "5449411" "5647953" "5676759").PN. OR ("5812403").URPN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/26 21:47
S8	16	("5812403" "5817576" "5976260").PN. OR ("6300255").URPN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/26 21:59
S9	31	S7 and decompos\$6	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/26 22:00
S10	36	S7 and (decompos\$6 OR break\$4 down OR breakdown)	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/26 22:01
S11	30	"4737474" "4842892" "4902645" "4951601" "4966869" "5231056" "5272112" "5326723" "5436200" "5447887" "5500249").PN. OR ("5817576").URPN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/26 22:09

S12	1214	(decompos\$ OR break\$ down OR breakdown) WITH (mix\$4 OR combin\$8) WITH (vapor\$4 OR vapour\$4 OR gas) AND (oxide).ab.	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/26 22:16
S13	431	(decompos\$ OR break\$ down OR breakdown) WITH (mix\$4 OR combin\$8) WITH (vapor\$4 OR vapour\$4 OR gas) AND (oxide).ab. AND (mix\$4 OR combin\$8) WITH (vapor\$4 OR vapour\$4 OR gas) WITH (unit OR compartment OR chamber OR part OR assembly OR cavity OR cell)	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/26 22:18
S14	195	(decompos\$ OR break\$ down OR breakdown) WITH (mix\$4 OR combin\$8) WITH (vapor\$4 OR vapour\$4 OR gas) AND (oxide) WITH (film OR layer OR coat\$4).ab. AND (mix\$4 OR combin\$8) WITH (vapor\$4 OR vapour\$4 OR gas) WITH (unit OR compartment OR chamber OR part OR assembly OR cavity OR cell)	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/26 22:19
S15	58	"3311668" "3895135" "4438021" "4500562" "4556584" "4945856" "4951601" "4986216" "5028573" "5079031" "5121706" "5270082" "5310858" "5355832" "5424097" "5447570" "5491112" "5522933" "5534068" "5536317" "5536319" "5536321" "5536322" "5536892" "5538758" "5554570" "5556473" "5582866" "5705726" "5709753").PN. OR ("6086952"). UPPN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/26 22:27

S16	50	"3311668" "3895135" "4123308" "4176209" "4438021" "4500562" "4556584" "4769505" "4921723" "4945856" "4951601" "4986216" "5028573" "5079031" "5083858" "5121706" "5270082" "5310858" "5355832" "5424097" "5447570" "5491112" "5522933" "5534068" "5536317" "5536319" "5536321" "5536322" "5536892" "5538758" "5554570" "5556473" "5582866" "5705726" "5709753" "5888905" "5958510" "6030706" "6051321" "6086952" "6107184" "6123993").PN. OR ("6362115").URPN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/26 22:29
S17	29	"4220460" "4276243" "5322710" "5562776" "5674574" "5702532" "5764849" "5820922" "5832177" "5868159" "5876503" "5945162" "5966499" "6072939" "6086952" "6110531" "6136725" "6161398" "6185370" "6225007" "6242771" "6271498").PN. OR ("6701066").URPN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/26 22:31
S18	57	"4895709" "5003092" "5139825" "5178911" "5192589" "5204314" "5209979" "5225561" "5280012" "5344792" "5362328" "5389401" "5399379" "5409735" "5453494" "5478610" "5514822" "5527567" "5536323" "5559260" "5616754" "5625587" "5637527" "5924012").PN. OR ("6159855").URPN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/26 22:33
S21	1	("20030178144").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2010/08/26 22:45
S22	19	("5030319" "5783495").PN. OR ("6372657"). URPN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/26 22:49
S23	1	("6713127").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2010/08/26 22:54
S24	18	("6713127").URPN.	USPAT	ADJ	ON	2010/08/26 22:54
S25	2	("5445676" "6185839").PN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/26 22:56

S26	20	"4389973" "4813373" "4854264" "4942057" "5016566" "5447569" "5541407").PN. OR ("5764849").URPN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/26 23:03
S27	83	"3608821" "3658304" "4263335" "4748043" "4792463" "4965090" "4993361" "5120703" "5138520" "5204314" "5229171" "5238709" "5250383" "5258204" "5262396" "5278138" "5316579" "5316800" "5344676" "5372754" "5399388" "5401680" "5423285" "5439845" "5456945" "5468679" "5478610" "5519234" "5534309" "5540959" "5595606" "5614252" "5863619" "5888583").PN. OR ("6110531").URPN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/26 23:21
S28	19	(decompo\$6 OR break\$4 down OR breakdown OR pyrolysis) WITH (mix\$4 OR combining OR combination) WITH (vapor\$4 OR vapour\$4 OR gas) AND 427/255.19.ccls.	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/26 23:51
S29	22	(decompo\$6 OR break\$4 down OR breakdown OR pyrolysis) WITH (mix\$4 OR combining OR combination OR combined) WITH (vapor\$4 OR vapour\$4 OR gas) AND 427/255.19.ccls.	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/26 23:51
S30	3352	(decompo\$6 OR break\$4 down OR breakdown OR pyrolysis) WITH (mix\$4 OR combining OR combination OR combined) WITH (vapor\$4 OR vapour\$4 OR gas) and oxide WITH (film OR layer OR coat\$4)	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/26 23:53
S31	452	(decompo\$6 OR break\$4 down OR breakdown OR pyrolysis) WITH (mix\$4 OR combining OR combination OR combined) WITH (vapor\$4 OR vapour\$4 OR gas) and oxide WITH (film OR layer OR coat\$4).ab.	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/26 23:53
S32	152	(decompo\$6 OR break\$4 down OR breakdown OR pyrolysis) WITH (mix\$4 OR combining OR combination OR combined) WITH (vapor\$4 OR vapour\$4 OR gas) and oxide WITH metal\$4 WITH (film OR layer OR coat\$4).ab.	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/26 23:54

S33	40	(decompos\$ OR break\$4 down OR breakdown OR pyrolysis) WITH (mix\$4 OR combining OR combination OR combined) WITH (vapor\$4 OR vapour\$4 OR gas) and 118/715.cds. and oxide WITH (film OR coat\$4 OR layer).bsum.	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/26 23:59
S34	0	(decompos\$ OR break\$4 down OR breakdown OR pyrolysis) WITH (vapor\$4 OR vapour\$4 OR gas) and 118/7195.cds. and oxide WITH (film OR coat\$4 OR layer).bsum.	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/27 00:02
S35	75	(decompos\$ OR break\$4 down OR breakdown OR pyrolysis) WITH (vapor\$4 OR vapour\$4 OR gas) and 118/719.cds. and oxide WITH (film OR coat\$4 OR layer).bsum.	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/27 00:02
S36	104	(decompos\$ OR break\$4 down OR breakdown OR pyrolysis) WITH (vapor\$4 OR vapour\$4 OR gas) WITH (prior OR before) WITH (diffuser OR plate OR showerhead OR shower?head)	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/27 00:09
S37	47	(decompos\$ OR break\$4 down OR breakdown OR pyrolysis) WITH (vapor\$4 OR vapour\$4 OR gas) WITH (prior OR before) WITH (diffuser OR plate OR showerhead OR shower?head) and oxide	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/27 00:09
S38	93	("4401054" "4534842" "4563367" "4745337" "5061838" "5102687" "5223457" "5227695" "5478403" "5483919" "5536914" "5605637" "5653811" "5666023" "5702530" "5762714" "5916365" "6054016" "6080446" "6103304" "6200893" "6428859").PN. OR ("6569501").URPN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/27 00:11
S39	4856	(decompos\$ OR break\$4 down OR breakdown OR pyrolysis) WITH (vapor\$4 OR vapour\$4 OR gas) WITH (mix\$5 OR combination OR combining OR combine OR combined) SAME (compartment OR cell OR unit OR chamber OR assembly)	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/27 00:38

S40	182	(decompos\$ OR break\$4 down OR breakdown OR pyrolysis) WITH (vapor\$4 OR vapour\$4 OR gas) WITH (mix\$5 OR combination OR combining OR combine OR combined) SAME (compartment OR cell OR unit OR chamber OR assembly) AND (oxide OR oxygen\$4) WITH (film OR layer OR coat\$4).ab.	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/27 00:39
S41	7	(decompos\$ OR break\$4 down OR breakdown OR pyrolysis) WITH (vapor\$4 OR vapour\$4 OR gas) WITH (mix\$5 OR combination OR combining OR combine OR combined) WITH (remote\$4 OR separate\$4) AND (oxide OR oxygen\$4) WITH (film OR layer OR coat\$4).ab.	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/27 00:41
S42	45	(decompos\$ OR break\$4 down OR breakdown OR pyrolysis) WITH (vapor\$4 OR vapour\$4 OR gas) WITH (mix\$5 OR combination OR combining OR combine OR combined) WITH (remote\$4 OR separate\$4) AND (oxide OR oxygen\$4) WITH (film OR layer OR coat\$4).absum.	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/27 00:42
S43	31	"3825439" "3916034" "4220488" "4434188" "4461783" "4521447" "4522663" "4569697" "4582560").PN. OR ("4716048").UPPN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/27 00:45
S44	146	"4138306" "4151325" "4178877" "4282267" "4352834" "4365587" "4366208" "4504518" "4532199" "4535000" "4557943" "4657774" "4678679" "4689093" "4701349" "4702934" "4716048" "4717584" "4717585" "4717586" "4718976" "4726963" "4728528" "4759947" "4772486" "4774195" "4778692" "4784874" "4792378" "4798165" "4801468" "4803093" "4818560" "4818563" "4835005" "4844950" "4851302" "4853251" "4869923" "4869924" "4870030" "4876983" "4885067" "4886683" "4888062" "4888088" "4898118" "4900694" "4908329"	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/27 01:00

		"4908330" "4913929" "4914052" "4926229" "4927786" "4937094" "4946514" "4951602" "4954397" "4957772" "4959106" "4971832" "4977106" "4987102" "4992305" "4992839" "4998503" "5002617" "5002618" "5002793" "5002796" "5006180" "5007971" "5008726" "5010842" "5018479" "5024706" "5028488" "5030475" "5037666" "5039354" "5061511" "5073232" "5084412" "5085885" "5087542" "5093149" "5093150" "5093710" "5100495" "5122431" "5126169" "5130170" "5139825" "5141613" "5151296" "5154135" "5173327" "5175017" "5178904" "5178905" "5180435" "5213997" "5220181" "5268034" "5296404" "5342652" "5356476" "5370739" "5378501" "5434110").PN. OR ("5593511"). URPN.				
S45	55	"0458762" "0545656" "0693496" "2077725" "4264393" "4270999" "4316791" "4367114").PN. OR ("4718976").URPN.	US-PGPUB; USPAT; USCCR	ADJ	ON	2010/08/27 01:01
S46	62564	(oxide OR oxygen\$4) WITH (film OR coat\$4 OR layer).ab.	US-PGPUB; USPAT; USCCR	ADJ	ON	2010/08/27 01:05
S47	2803	S46 and MOCVD OR organo WITH CVD	US-PGPUB; USPAT; USCCR	ADJ	ON	2010/08/27 01:05
S48	4291	S46 and (MOCVD OR organometallic OR organo? metallic OR metal\$4 organ\$4 adj3 vapo\$2)	US-PGPUB; USPAT; USCCR	ADJ	ON	2010/08/27 01:06
S49	2036	S48 and (break\$4 down OR breakdown OR decompos\$6 OR pyroly\$4)	US-PGPUB; USPAT; USCCR	ADJ	ON	2010/08/27 01:07
S50	61	S48 and (break\$4 down OR breakdown OR decompos\$6 OR pyroly\$4) WITH (remote\$4 OR separate\$5)	US-PGPUB; USPAT; USCCR	ADJ	ON	2010/08/27 01:07
S51	76	S48 and (break\$4 down OR breakdown OR decompos\$6 OR pyroly\$4) WITH (remote\$4 OR separate\$5 OR outside)	US-PGPUB; USPAT; USCCR	ADJ	ON	2010/08/27 01:07

SS2	84	(oxide OR oxygen\$4) WITH (film OR coat\$4 OR layer).ab. and 118/719.ccls.	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/27 01:09
SS3	86	(oxide OR oxygen\$4 OR dioxide OR monoxide) WITH (film OR coat\$4 OR layer).ab. and 118/719.ccls.	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/27 01:09
SS4	1	("6319327").URPN.	USPAT	ADJ	ON	2010/08/27 01:16
SS5	38	"20020166507" "4514441" "4951603" "5155658" "5478610" "5500988" "5536323" "5555154" "5595606" "5641540" "5653806" "5766364" "5817170" "5876503" "6039465" "6051286" "6066204" "6074487" "6077715" "6090210" "6106625" "6126753" "6161500" "6176929" "6179920" "6190728" "6204204" "6258157" "6281022" "6312816" "6325017" "6419994" "6428850" "6470144").PN. OR ("6756235").URPN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/27 01:19
SS6	1192	(decompo\$6 OR break\$4 down OR breakdown OR pyrolysis) WITH (vapor\$4 OR vapour\$4 OR gas) WITH (mix OR mixture OR combination OR combined) and oxide WITH (film OR coat\$4 OR layer).bsum.	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/27 01:26
SS7	309	(decompo\$6 OR break\$4 down OR breakdown OR pyrolysis) WITH (vapor\$4 OR vapour\$4 OR gas) WITH (mix OR mixture OR combination OR combined) and oxide WITH (film OR coat\$4 OR layer).ab.	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/27 01:26
SS8	67	("3306768" "4471525" "4569701" "4604150" "4656497" "4676847" "4818560" "4835005" "4845054" "4907047" "4971926" "5066609" "5160988" "5173440" "5227329" "5270244" "5272102" "5283453" "5292679" "5292692" "5310698" "5360646").PN. OR ("5451809" "5462899"). URPN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/27 01:29

S59	28	"4260647" "4872947" "5000113" "5271972" "5286518" "5319247" "5362526" "5393708" "5426076" "5462899" "5502006" "5593741").PN. OR ("6009827"). URPN.	US-PGPUB; USPAT; USCCR	ADJ	ON	2010/08/27 01:38
S60	1	"5000113").PN.	US-PGPUB; USPAT; USCCR	OR	OFF	2010/08/27 01:48
S61	137	S46 and heat\$4 WITH (channel OR line OR tube OR pipe) WITH (mixture OR combination OR combined OR mix) WITH (vapor OR gas OR vapour)	US-PGPUB; USPAT; USCCR	ADJ	ON	2010/08/27 01:53
S62	10	premix\$4 SAME TEOS SAME CVD	US-PGPUB; USPAT; USCCR	ADJ	ON	2010/08/27 02:05
S63	123	premix\$4 SAME CVD and (silicon oxide OR silicon dioxide OR "sio.sub.2")	US-PGPUB; USPAT; USCCR	ADJ	ON	2010/08/27 02:05
S64	113	(premix\$4 OR pre?mix\$4) WITH (gas OR vapor OR vapour) SAME CVD and (silicon oxide OR silicon dioxide OR "sio.sub.2")	US-PGPUB; USPAT; USCCR	ADJ	ON	2010/08/27 02:06
S65	23	"20010041462" "20010046792" "20010049080" "20030106495" "3934117" "4544416" "5225378" "5234501" "5331134" "5669768" "5777300" "5810929" "6221791" "6239044" "6287984" "6335295" "6369361" "6391738" "6516143" "6540509" "6589349").PN. OR ("6884295"). URPN.	US-PGPUB; USPAT; USCCR	ADJ	ON	2010/08/27 02:34
S66	114	(premix\$4 OR pre?mix\$4) WITH (gas\$4 OR vapor OR vapour) SAME CVD and (silicon oxide OR silicon dioxide OR "sio.sub.2")	US-PGPUB; USPAT; USCCR	ADJ	ON	2010/08/27 02:44
S67	55	(premix\$4 OR pre?mix\$4) WITH (gas\$4 OR vapor OR vapour) AND CVD and (silicon oxide OR silicon dioxide OR "sio.sub.2").ab.	US-PGPUB; USPAT; USCCR	ADJ	ON	2010/08/27 02:46
S68	140	S46 and heat\$4 WITH (channel OR line OR tube OR pipe) WITH (mixture OR combination OR combined OR mix) WITH (gas\$4)	US-PGPUB; USPAT; USCCR	ADJ	ON	2010/08/27 02:49

S69	13	S68 not S61	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/27 02:49
S70	14	"3923484" "4411678" "4469045" "4828880" "4910088").PN. OR ("5089039"). URPN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/27 02:55
S71	92	heat\$4 SAME (premix\$4 OR pre?mix\$4) WITH (gas\$4 OR vapor OR vapour) AND CVD and (silicon oxide OR silicon dioxide OR "sio.sub.2")	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/27 03:03
S72	8	(decompos\$4 OR activat\$4 OR break\$ down OR breakdown) SAME (premix\$4 OR pre?mix\$4) WITH (gas\$4 OR vapor OR vapour) AND oxide WITH (film OR layer OR coat\$4).ab.	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/27 03:07
S73	50	(heat\$4) SAME (premix\$4 OR pre?mix\$4) WITH (gas\$4 OR vapor OR vapour) AND oxide WITH (film OR layer OR coat\$4).ab.	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/27 03:08
S74	38	"20020166507" "4514441" "4951603" "5155658" "5478610" "5500988" "5536323" "5555154" "5595606" "5641540" "5653806" "5766364" "5817170" "5876503" "6039465" "6051286" "6066204" "6074487" "6077715" "6090210" "6106625" "6126753" "6161500" "6176929" "6179920" "6190728" "6204204" "6258157" "6281022" "6312816" "6325017" "6419994" "6428850" "6470144").PN. OR ("6756235").URPN.	US-PGPUB; USPAT; USOCR	ADJ	ON	2010/08/27 03:16

EAST Search History (Interference)

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